Phase formation of Ti$_{1-x}$Al$_x$N thin films by combinatorial magnetron sputtering

Sida Liu, Keke Chang, Jochen M. Schneider

Materials Chemistry, RWTH Aachen University, D-52074 Aachen, Germany

Ti-Al-N thin film materials, as promising high-performance industrial benchmark coatings, still have great room for thermal stability and mechanical property improvements. In this work, the metastable phase formation diagram of Ti$_{1-x}$Al$_x$N thin films is obtained by combinatorial magnetron sputtering. The thermodynamics and kinetics of this system are investigated systematically by applying ab initio and the CALPHAD approach.